



wherein R_1 is a hydrogen atom or methyl, R_2 is an acid-labile tertiary alkyl group, and $m/(m+n)$ is 0.5 to 0.8.

5. A resist composition comprising:

(a) a photosensitive copolymer having a weight-average molecular weight of 3,000 to 100,000 and consisting essentially of first and second monomers represented by the following formulae:

Sub
B2

